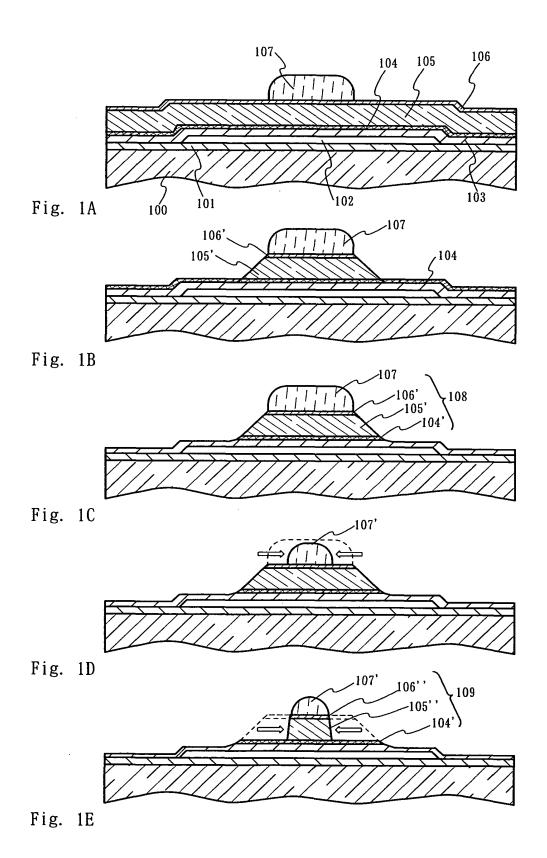
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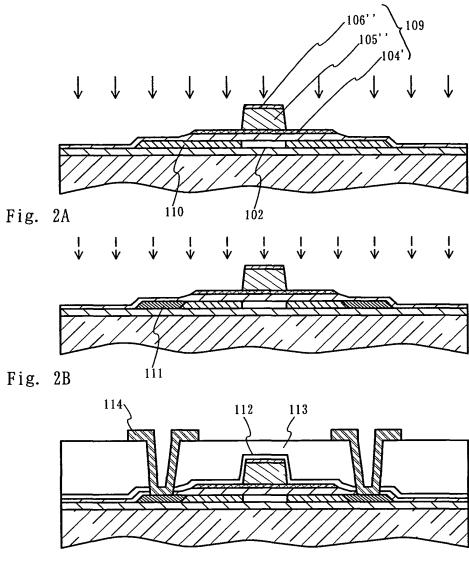


Fig. 2C

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**DEVICE** 

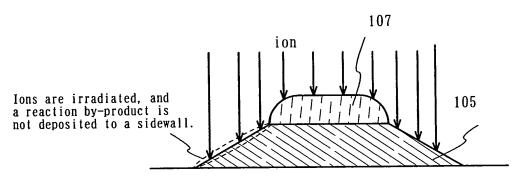


Fig. 3A

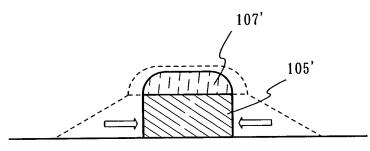


Fig. 3B

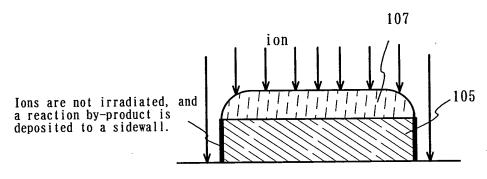


Fig. 4A

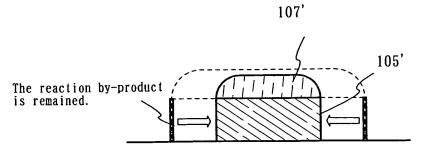
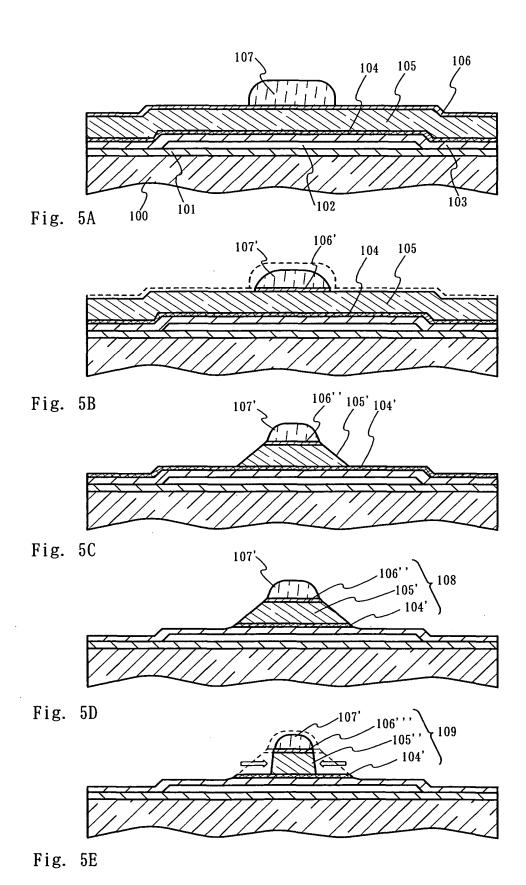


Fig. 4B

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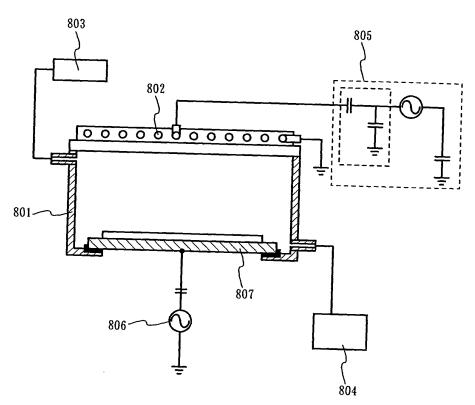
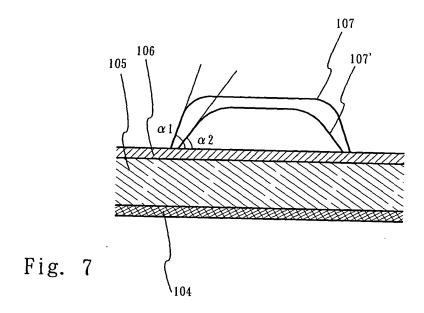


Fig. 6



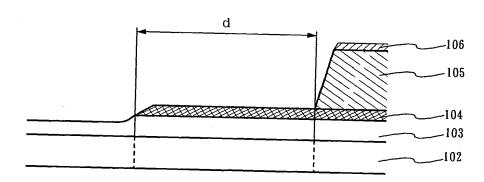
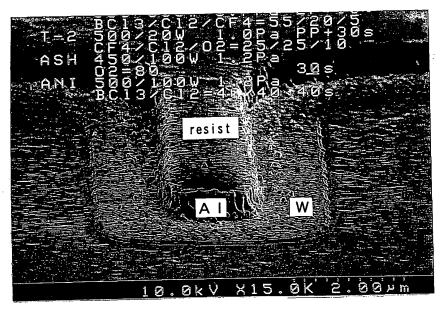


Fig. 8

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FiG. 9

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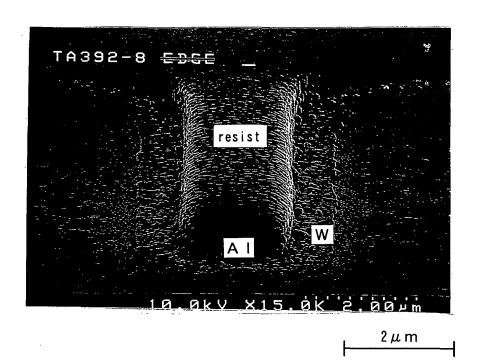


FiG. 10

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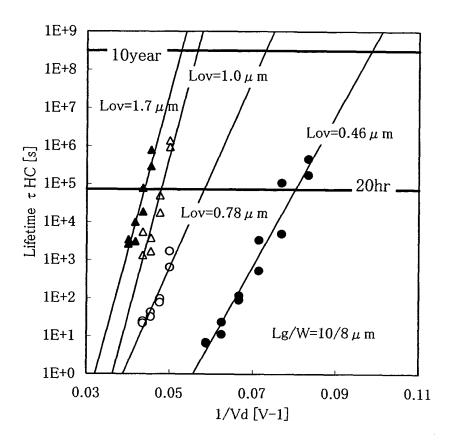


FiG. 11

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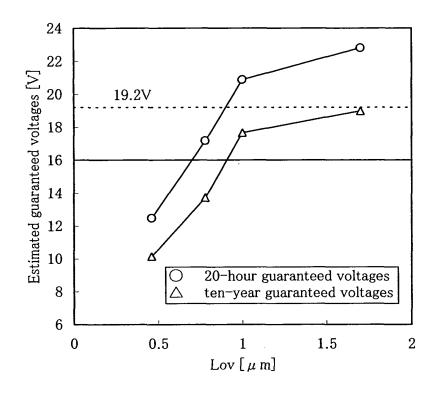


FiG. 12

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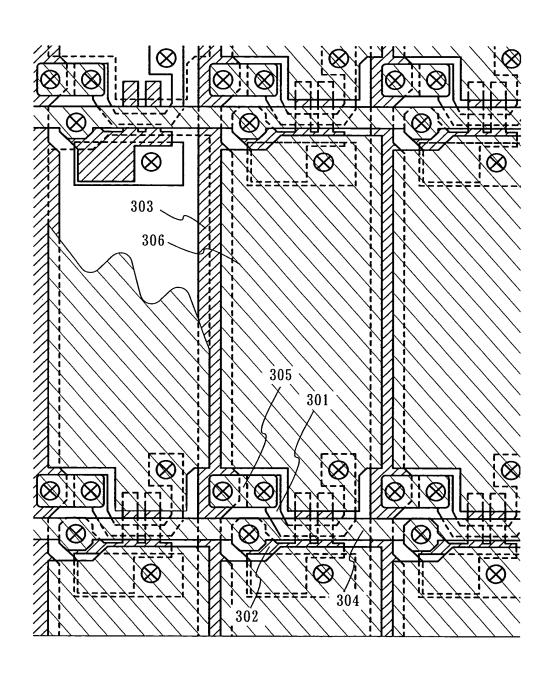


FiG. 13

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